

# Supporting Information

## Molecular Glass Resists based on 9,9'-Spirobifluorene Derivatives: Pendant Effect and Comprehensive Evaluation in EUV Lithography

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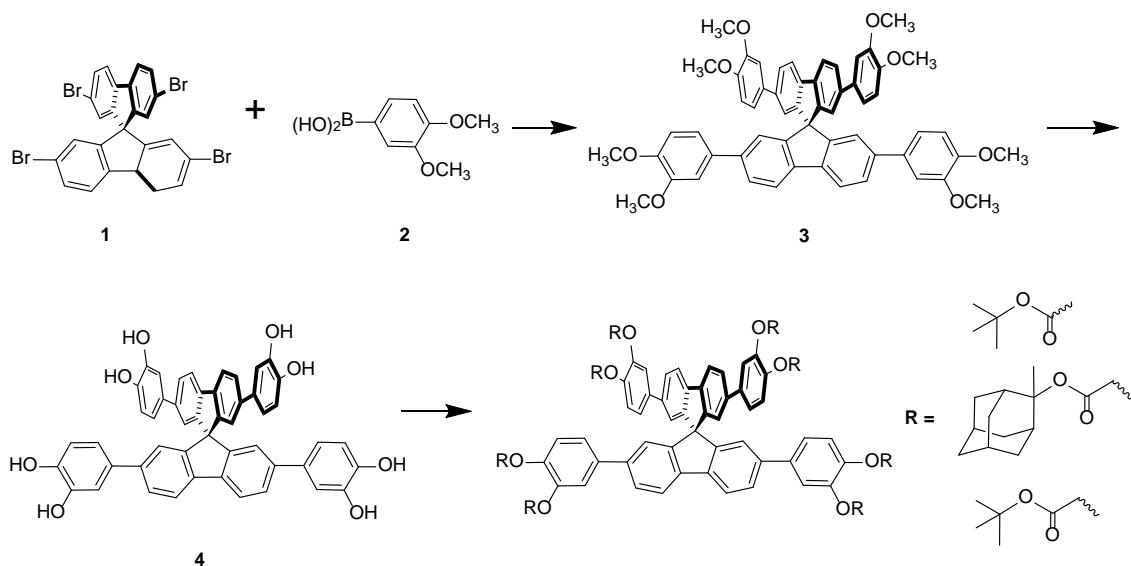
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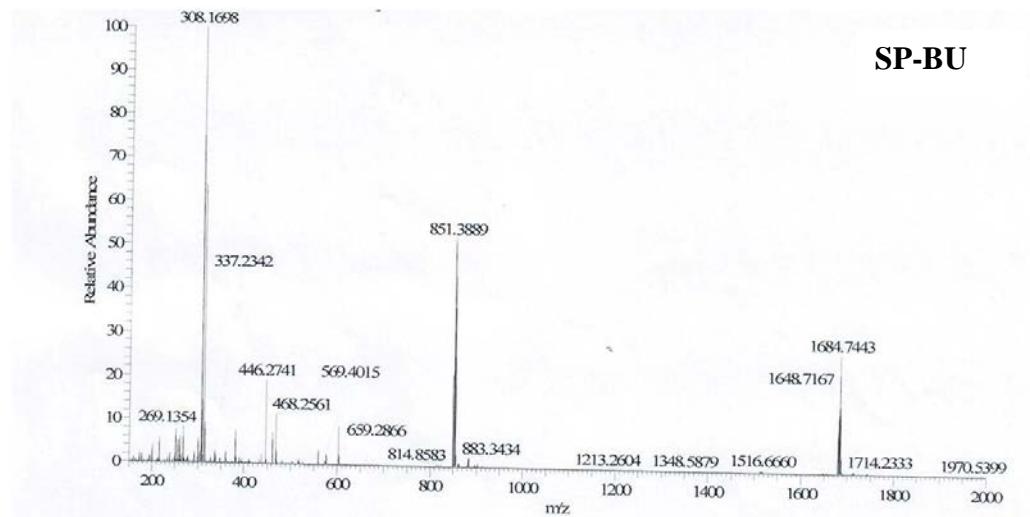
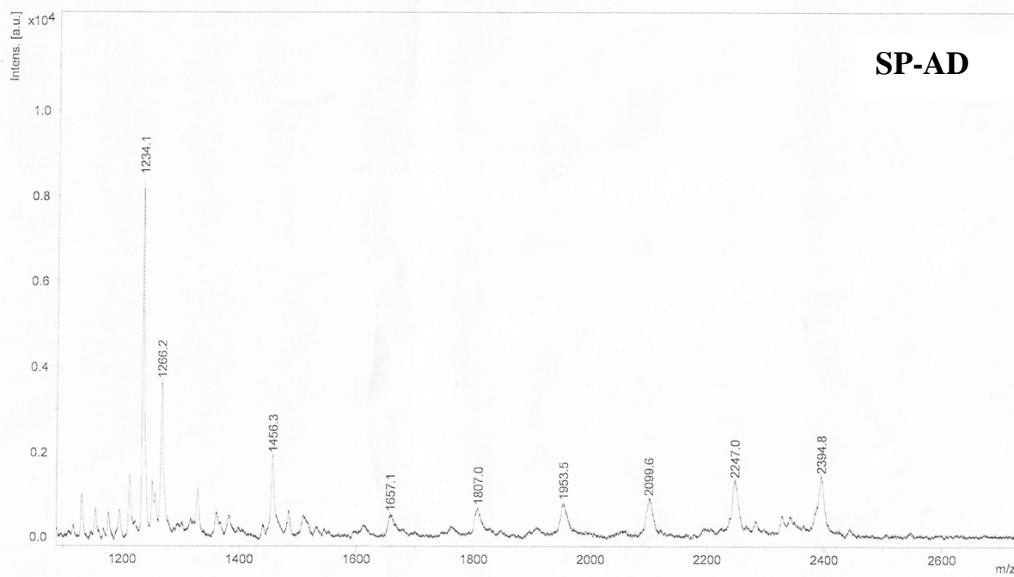
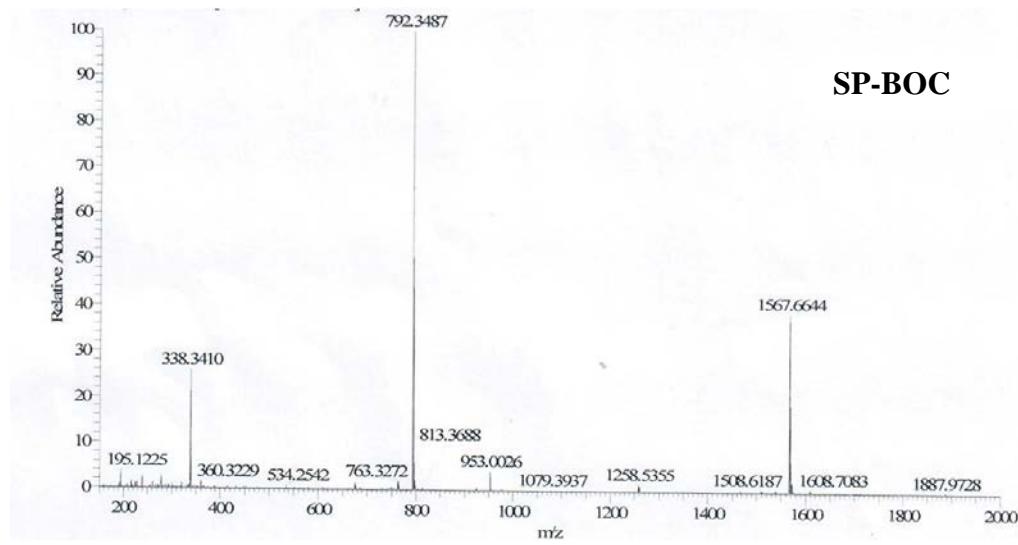
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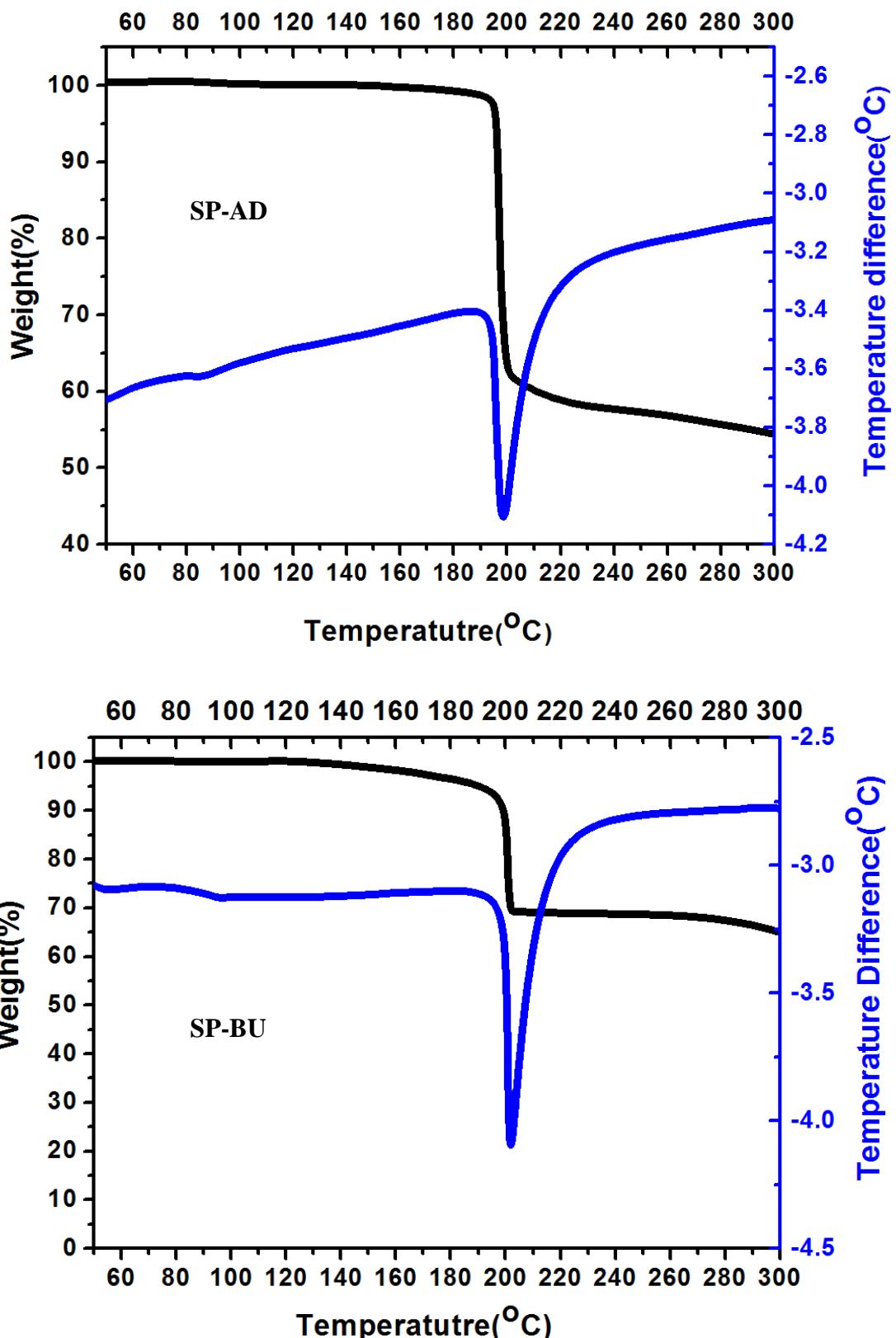
Synthesis of MGs. MS spectra, TG and DSC curves, Schematic deprotection reactions, and SEM images.



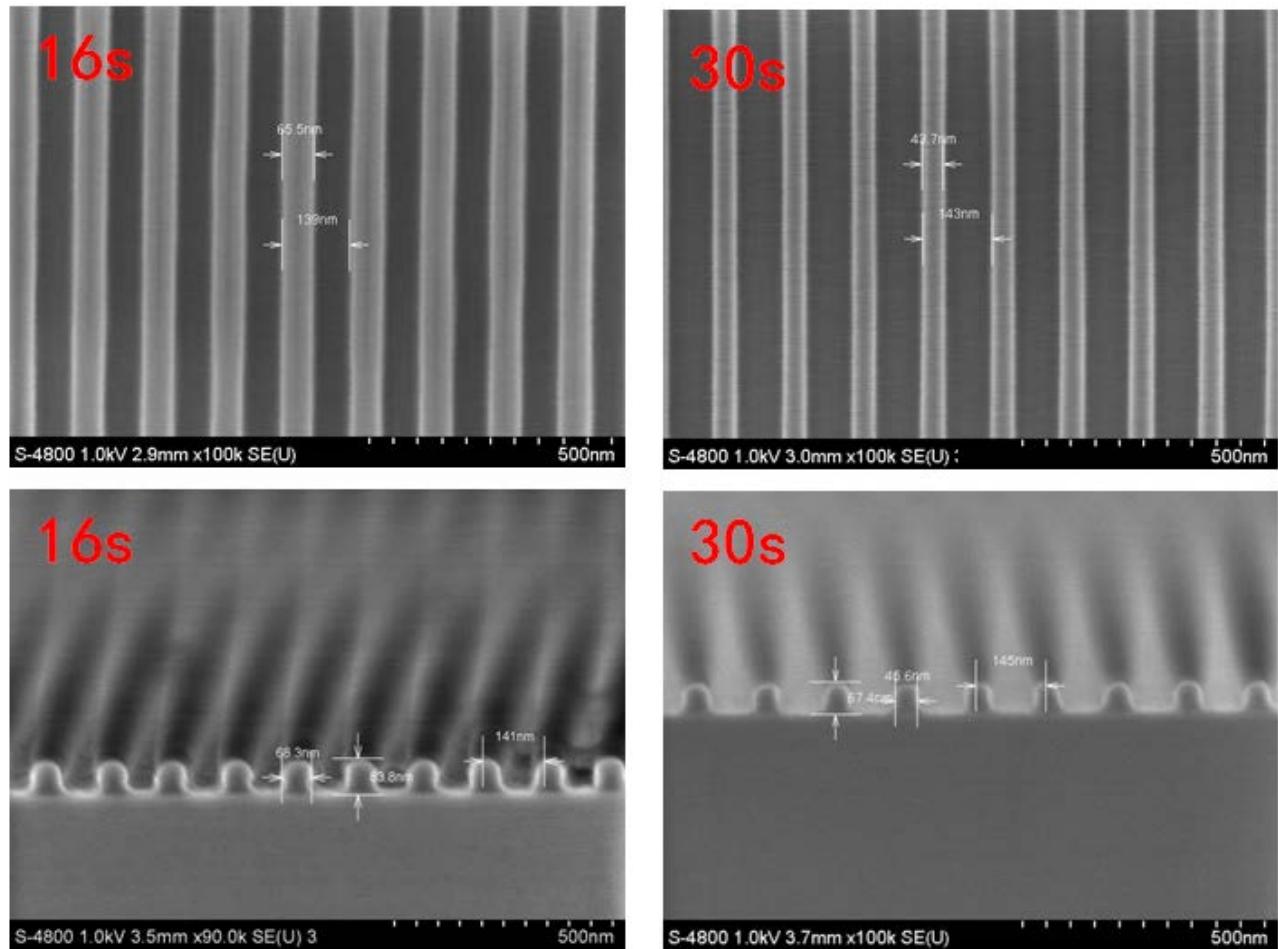
**Scheme S1.** Synthesis of the MGs.



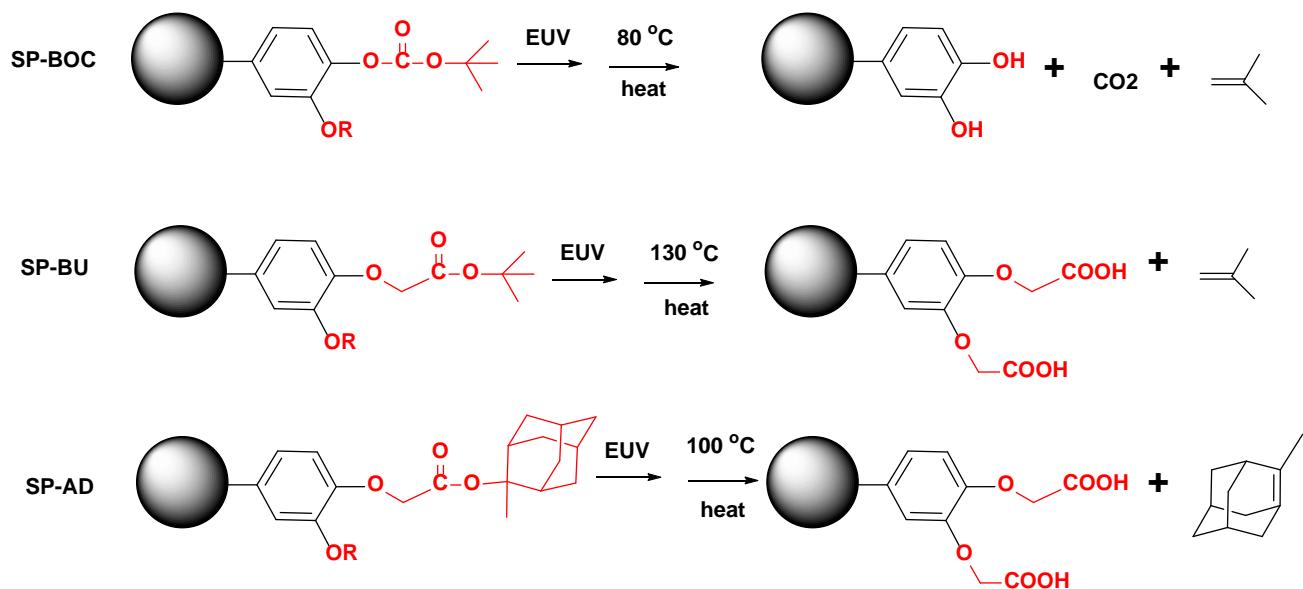
**Figure S1.** MS spectra of SP derivatives



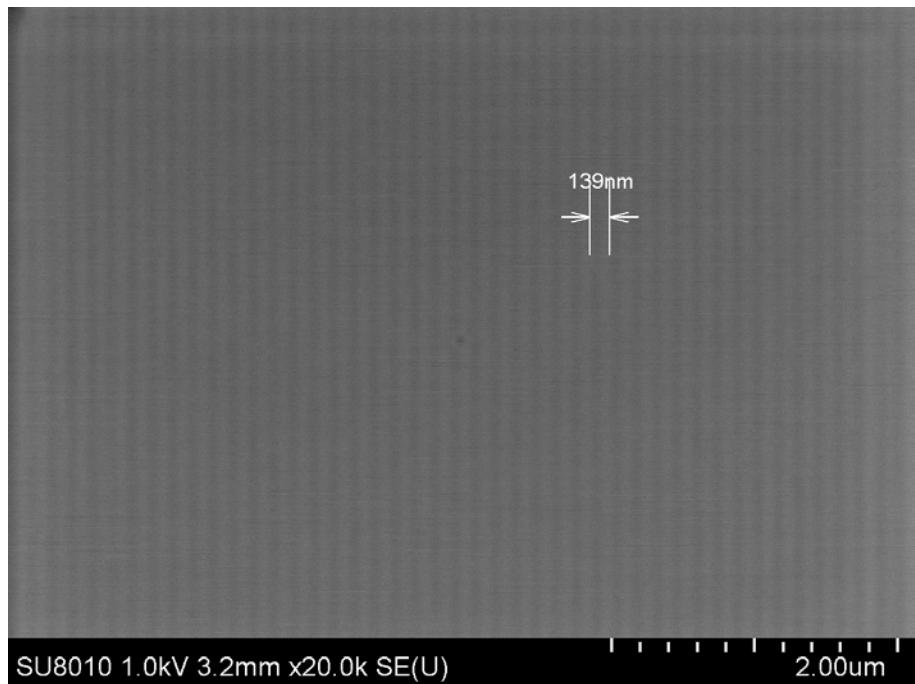
**Figure S2.** TG and DSC curves of SP-AD and SP-BU



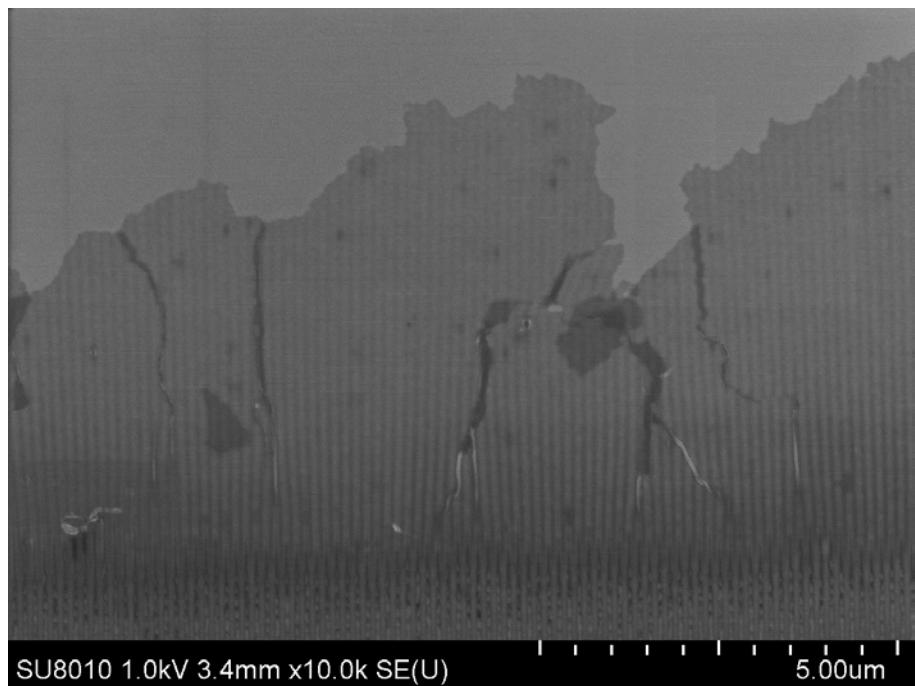
**Figure S3.** SEM images of the lines (up) and corresponding cross-section (bottom) patterns at exposure time of 16s and 30s, thickness of the dense lines is about 80nm and 67nm.



**Figure S4.** Schematic deprotection for the **SP-BOC**, **SP-BU** and **SP-AD** resist



**Figure S5.** SEM image of line-space patterns (top view) for **SP-AD** resist



**Figure S6.** SEM image of fractured film of **SP-AD**